

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Applicant(s): N. HASEGAWA, et al.  
Application No.: TBD  
Filed: October 17, 2003  
For: MANUFACTURING METHOD OF PHOTOMASK AND  
PHOTOMASK  
Expected  
Group: 1756  
Expected  
Examiner: K. Sagar

**CLAIM FOR PRIORITY**

Mail Stop Patent Application  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

October 17, 2003

Sir:

Pursuant to the requirements of 35 USC §119 and 37 CFR §1.55, Applicants  
hereby claim the right of priority based on Japanese Patent Application  
No. 2000-206729, filed in Japan on July 7, 2000.

A certified copy of the above-identified Japanese Patent Application was  
submitted on June 18, 2001, in prior Application No. 09/881,701, filed  
June 18, 2001.

Respectfully submitted,

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WIS/sjg